ABSTRACT OF THE DISCLOSURE

A semiconductor integrated circuit device comprises a semiconductor substrate; an insulating layer formed on the semiconductor substrate; a semiconductor layer insulated from the semiconductor substrate by the insulating layer; source regions of a first conduction type and drain regions of the first conduction type both formed in the semiconductor layer; body regions of a second conduction type formed in the semiconductor layer between the source regions and the drain regions to store data by accumulating or releasing an electric charge; word lines formed on the body regions in electrical isolation from the body regions to extend in a first direction; bit lines connected to the drain regions and extending in a direction different from the first direction; and buried wirings formed in the insulating layer in electrical isolation from the semiconductor substrate and the semiconductor layer, said buried wirings extending in parallel with the bit lines.

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